Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1905	(430/1 or 430/2 or 359/3 or 359/12).ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/16 15:32
L2	38	l1 and (pdlc or ((polymer near5 dispersed) near5 (lc or crystal$1)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/16 15:34
L3	5	(copy or copying or copied or (contact near5 expos$6)) and l2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/16 15:35

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                   data from INPADOC
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 NEWS  6  MAR 03   REGISTRY/ZREGISTRY - Sequence annotations enhanced
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 NEWS  8  MAR 22   KOREAPAT now updated monthly; patent information enhanced
 NEWS  9  MAR 22   Original IDE display format returns to REGISTRY/ZREGISTRY
 NEWS  10 MAR 22   PATDPASPC - New patent database available
 NEWS  11 MAR 22   REGISTRY/ZREGISTRY enhanced with experimental property tags
 NEWS  12 APR 04   EPFULL enhanced with additional patent information and new
                   fields
 NEWS  13 APR 04   EMBASE - Database reloaded and enhanced
 NEWS  14 APR 18   New CAS Information Use Policies available online
 NEWS  15 APR 25   Patent searching, including current-awareness alerts (SDIs),
                   based on application date in CA/CAplus and USPATFULL/USPAT2
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                   applications.
 NEWS  16 APR 28   Improved searching of U.S. Patent Classifications for
                   U.S. patent records in CA/CAplus
 NEWS  17 MAY 23   GBFULL enhanced with patent drawing images
 NEWS  18 MAY 23   REGISTRY has been enhanced with source information from
                   CHEMCATS
 NEWS  19 JUN 06   The Analysis Edition of STN Express with Discover!
                   (Version 8.0 for Windows) now available
 NEWS  20 JUN 13   RUSSIAPAT: New full-text patent database on STN
 NEWS  21 JUN 13   FRFULL enhanced with patent drawing images
 NEWS  22 JUN 27   MARPAT displays enhanced with expanded G-group definitions
                   and text labels
 NEWS  23 JUL 01   MEDICONF removed from STN
 NEWS  24 JUL 07   STN Patent Forums to be held in July 2005
 NEWS  25 JUL 13   SCISEARCH reloaded
 NEWS  26 JUL 20   Powerful new interactive analysis and visualization software,
                   STN AnaVist, now available
 NEWS  27 AUG 11   Derwent World Patents Index(R) web-based training during
                   August
 NEWS  28 AUG 11   STN AnaVist workshops to be held in North America

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               MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP),
               AND CURRENT DISCOVER FILE IS DATED 13 JUNE 2005

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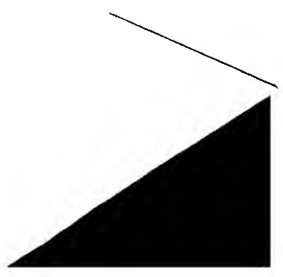

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           819 PDLC
           169 PDLCS
           884 PDLC
                 (PDLC OR PDLCS)
       1020028 POLYMER
        840995 POLYMERS
       1381077 POLYMER
                 (POLYMER OR POLYMERS)
        604841 DISPERS?
         32805 LC
          1228 LCS
         33413 LC
                 (LC OR LCS)
         11200 LCD
          1147 LCDS
         11697 LCD
                 (LCD OR LCDS)
        691088 LIQUID
        123676 LIQUIDS
        784645 LIQUID
                 (LIQUID OR LIQUIDS)
        964955 LIQ
         92015 LIQS
       1000835 LIQ
                 (LIQ OR LIQS)
       1384151 LIQUID
                 (LIQUID OR LIQ)
       1171264 CRYSTAL
        617496 CRYSTALS
       1444992 CRYSTAL
                 (CRYSTAL OR CRYSTALS)
          2529 (POLYMER(4A)DISPERS?)(5A)(LC OR LCD OR (LIQUID(4A)CRYSTAL))
L1        2603 (PDLC OR ((POLYMER(4A)DISPERS?)(5A)(LC OR LCD OR (LIQUID(4A)CRYS
               TAL))))
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=> s (copy? or copied or master? or (contact(5a)expos?)) and l1
         60812 COPY?
          2863 COPIED
         29897 MASTER?
        445801 CONTACT
        108018 CONTACTS
        501678 CONTACT
                 (CONTACT OR CONTACTS)
        761304 EXPOS?
          6694 CONTACT(5A)EXPOS?
L2           5 (COPY? OR COPIED OR MASTER? OR (CONTACT(5A)EXPOS?)) AND L1

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         60812 COPY?
          2863 COPIED
         29897 MASTER?
         32531 DUPLICAT?
        445801 CONTACT
        108018 CONTACTS
        501678 CONTACT
                 (CONTACT OR CONTACTS)
        761304 EXPOS?
          6694 CONTACT(5A)EXPOS?
L3           5 (COPY? OR COPIED OR MASTER? OR DUPLICAT? OR (CONTACT(5A)EXPOS?))
                 AND L1

=> d all 1-5

L3   ANSWER 1 OF 5  CAPLUS  COPYRIGHT 2005 ACS on STN
AN   2004:360257  CAPLUS
DN   140:383146
ED   Entered STN:  04 May 2004
TI   System and method for replicating volume holograms
IN   Sutherland, Richard L.; Sappington, John; Brandelik, Donna M.; Siwecki,
     Stephen A.; Shepherd, Christina K.; Pogue, Robert T.
PA   Science Applications International Corporation, USA
SO   U.S., 29 pp.
     CODEN: USXXAM
DT   Patent
LA   English
IC   ICM  G03H001-02
INCL 430001000; 430002000; 359012000; 359003000
CC   74-8 (Radiation Chemistry, Photochemistry, and Photographic and Other
     Reprographic Processes)
FAN.CNT 1
     PATENT NO.          KIND   DATE        APPLICATION NO.        DATE
     --------------      ----   --------    -------------------    --------
PI   US 6730442           B1    20040504    US 2000-577166         20000524
     US 2004175627        A1    20040909    US 2004-796071         20040310
PRAI US 2000-577166       A1    20000524
CLASS
 PATENT NO.       CLASS  PATENT FAMILY CLASSIFICATION CODES
 --------------   -----  ----------------------------------------------
 US 6730442       ICM    G03H001-02
                  INCL   430001000; 430002000; 359012000; 359003000
 US 6730442       NCL    430/001.000; 359/003.000; 359/012.000; 430/002.000
                  ECLA   G02F001/1334H; G03H001/04F; G03H001/20; G03H001/28
 US 2004175627    NCL    430/001.000
                  ECLA   G02F001/1334H; G03H001/04F; G03H001/20; G03H001/28
AB   The present invention offers increased efficiency and quality in the
       ***duplication***   of a   ***master***   hologram utilizing an improved
     method of contact printing.  This improved method of contact printing
     employs a   ***polymer***  -  ***dispersed***     ***liq***  .
       ***crystal***   (  ***PDLC***  ) recording medium as the
       ***duplication***   blank and/or the   ***master***   hologram material.
     The optical qualities of the   ***PDLC***   material described herein
     provide an improved method of   ***duplication***   using single beam
     contact printing regardless of the material comprising the   ***master***
     hologram.  Thus,   ***master***   holograms originally recorded using
     highly complex optical geometries (e.g., computer generated holograms) are
     capable of   ***duplication***   without the need for multiple beam
```

power/intensity balancing and long recording times. The improved hologram contact printing method described herein works with virtually any type of ***master*** hologram, including both reflection and transmission holograms.

ST replicating vol holograms

IT Holography
Polymer - ***dispersed*** ***liquid*** ***crystals***
(system and method for replicating vol. holograms)

RE.CNT 136 THERE ARE 136 CITED REFERENCES AVAILABLE FOR THIS RECORD

RE

(1) Akashi; US 5354498 A 1994 CAPLUS
(2) Amako; US 5682214 A 1997 CAPLUS
(3) Anderson; US 5136666 A 1992
(4) Ando; US 5330264 A 1994
(5) Ando; US 5648857 A 1997
(6) Anon; EP 0087281 a 1983
(7) Anon; JP 60189729 A 1985
(8) Anon; JP 01-068784 a 1989
(9) Anon; JP 03-188479 a 1991
(10) Anon; WO 9727519 1997 CAPLUS
(11) Anon; EP 0856765 A1 1998 CAPLUS
(12) Anon; EP 0856766 A2 1998 CAPLUS
(13) Anon; EP 0856768 A2 1998 CAPLUS
(14) Anon; EP 0867749 A2 1998
(15) Anon; JP 10319237 1998 CAPLUS
(16) Anon; WO 9804650 a 1998 CAPLUS
(17) Anon; WO 9909440 1999
(18) Avant; US 5047039 A 1991
(19) Barak; US 4930674 A 1990
(20) Baues; US 4003629 A 1977
(21) Baues; US 4006963 A 1977
(22) Benton, S; SPIE 1979, V212, P2
(23) Benton, S; SPIE 1980, V215, P156
(24) Bischel; US 5544268 A 1996
(25) Bjelkhagen; US 5014709 A 1991
(26) Bjelkhagen, H; Applied Optics 1992, V31(8), P1041
(27) Bowley, C; Mol Cryst Liq 1999, V331, P209
(28) Brandstetter; US 5547786 A 1996
(29) Brumm; US 3758186 A 1973
(30) Buchkremer; US 5734485 A 1998
(31) Chang; US 4818045 A 1989
(32) Coates; US 5323251 A 1994 CAPLUS
(33) Crawford; US 5875012 A 1999 CAPLUS
(34) Crawford, G; SID International Symposium Digest of Applications Papers 1996, P99
(35) Crockard; US 5174276 A 1992
(36) Cushman; US 4983176 A 1991
(37) Damask; US 5915051 A 1999
(38) Deacon; US 5488681 A 1996
(39) Dejule; US 5363228 A 1994
(40) Dickson; US 5272550 A 1993
(41) Doane; US 4688900 A 1987
(42) Doane; US 5240636 A 1993 CAPLUS
(43) Doane; US 5384067 A 1995 CAPLUS
(44) Doane; US 5695682 A 1997 CAPLUS
(45) Domash; US 5937115 A 1999
(46) Doyle; US 5003386 A 1991
(47) Faris; US 5680233 A 1997 CAPLUS
(48) Fergason; US 4810063 A 1989
(49) Fergason; US 4856876 A 1989
(50) Gambogi; US 5930011 A 1999 CAPLUS
(51) Goosen; US 4018228 A 1977
(52) Grayzel; US 4809713 A 1989
(53) Gunjima; US 4818070 A 1989
(54) Haines; US 4832445 A 1989
(55) Hall; US 5471326 A 1995
(56) Haugh; US 3658526 A 1972 CAPLUS
(57) Healey; US 4923269 A 1990
(58) Heynderickx; US 5210630 A 1993
(59) Hirai; US 5235445 A 1993 CAPLUS
(60) Ingwall; US 5198912 A 1993 CAPLUS
(61) Jenkins; US 5661577 A 1997

(62) Jubb; US 5356557 A 1994 CAPLUS
(63) Jubb; US 5698134 A 1997 CAPLUS
(64) Kaster; US 4368736 A 1983
(65) Kaster; US 5234447 A 1993
(66) Kaster; US 5366462 A 1994
(67) Kato; US 5852504 A 1998
(68) Keys; US 4942102 A 1990 CAPLUS
(69) Kirsch; US 4929240 A 1990
(70) Kuhl; US 4124947 A 1978
(71) Leib; US 5227859 A 1993
(72) Leith; US 3580655 A 1971
(73) Lougnot, D; Pure Appl Opt 1993, V2, P383 CAPLUS
(74) Madden; US 5170925 A 1992
(75) Margerum; US 3694218 A 1972 CAPLUS
(76) Margerum; US 4938568 A 1990 CAPLUS
(77) Margerum; US 5096282 A 1992 CAPLUS
(78) Martin; US 5725970 A 1998
(79) McGrew; US 4832424 A 1989
(80) Metz; US 5166813 A 1992
(81) Mihailov; US 5706375 A 1998
(82) Mikhailov, V; SPIE 1997, V3011, P200 CAPLUS
(83) Miller; US 4891152 A 1990 CAPLUS
(84) Nakao; US 5015249 A 1991
(85) Narancic; US 4374371 A 1983
(86) Nerad; US 5593615 A 1997 CAPLUS
(87) Nerad; US 5641426 A 1997 CAPLUS
(88) Newswanger; US 5291317 A 1994
(89) Nicholson; US 4416540 A 1983
(90) Nishiwaki; US 4560249 A 1985
(91) Nishiwaki; US 4673241 A 1987
(92) Oddsen; US 5220928 A 1993
(93) Ortiz; US 5376095 A 1994
(94) O'Callaghan; US 5182665 A 1993
(95) Perlin; US 4210132 A 1980
(96) Phillips; US 4857425 A 1989
(97) Pollack; US 4045124 A 1977
(98) Popovich; US 6115152 A 2000 CAPLUS
(99) Popovich; US 6211976 B1 2001 CAPLUS
(100) Redfield; US 5529861 A 1996
(101) Reinhorn; US 6172778 B1 2001 CAPLUS
(102) Saburi; US 5313317 A 1994 CAPLUS
(103) Sansone; US 5084203 A 1992 CAPLUS
(104) Schellenberg; US 5105298 A 1992 CAPLUS
(105) Simpson; US 5047040 A 1991
(106) Siutherland; SPIE 1994, V2152, P303
(107) Stone; US 5771320 A 1998
(108) Stroke, G; Physics Letters 1966, V20(4), P368
(109) Sturdevant; US 3667946 A 1972 CAPLUS
(110) Suga; US 5453338 A 1995
(111) Sutherland; US 5698343 A 1997
(112) Sutherland; US 5942157 A 1999 CAPLUS
(113) Sutherland; SPIE 1995, V2404, P132 CAPLUS
(114) Sutherland, R; Chem Mater 1993, V5, P1533 CAPLUS
(115) Taketomi; US 5731853 A 1998 CAPLUS
(116) Tanaka; US 5748272 A 1998 CAPLUS
(117) Tanaka; US 5751452 A 1998 CAPLUS
(118) Tokuda, A; Applied Optics 1980, V19(13), P2219
(119) Tokumitsu; US 5227906 A 1993
(120) Tondiglia; Opt Lett 1995, V20(11), P1325 CAPLUS
(121) Tzakis; US 5188638 A 1993
(122) Vaz; US 4728547 A 1988 CAPLUS
(123) Von Bally, G; Applied Optics 1984, V23(11), P1725
(124) Wang; US 5270843 A 1993 CAPLUS
(125) Weitzel, K; Optics Letters 1997, V22(24)
(126) West; US 5264950 A 1993
(127) Wilk; US 5258008 A 1993
(128) Wilk; US 5330486 A 1994
(129) Winston; US 5303322 A 1994
(130) Wreede; US 5499118 A 1996
(131) Wu; US 5661533 A 1997 CAPLUS
(132) Yamagishi; US 5011624 A 1991 CAPLUS
(133) Yariv; US 5832148 A 1998

(134) Yokoya; US 5328800 A 1994 CAPLUS
(135) Zhang, J; J Am Chem Soc 1992, V114(4), P1506 CAPLUS
(136) Zhang, J; SPIE 1994, V2042, P238 CAPLUS

L3 ANSWER 2 OF 5 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1998:483253 CAPLUS
DN 129:189970
ED Entered STN: 04 Aug 1998
TI Effect of molar mass of an epoxy oligomer on the phase separation in epoxy based ***polymer*** ***dispersed*** ***liquid*** ***crystals***
AU Siddiqi, Humaira Masood; Dumon, Michel; Pascault, Jean Pierre
CS Laboratoire des Mat riaux Macromoleculaires UMR 5627 CNRS, Institut National des Sciences Appliquees, Villeurbanne, F- 69 621, Fr.
SO Journal of Materials Chemistry (1998), 8(8), 1691-1695
CODEN: JMACEP; ISSN: 0959-9428
PB Royal Society of Chemistry
DT Journal
LA English
CC 37-5 (Plastics Manufacture and Processing)
Section cross-reference(s): 75
AB ***Polymer*** ***dispersed*** ***liq*** . ***crystals*** based on epoxy-amine [DGEBA-Jeffamine D400] crosslinked matrixes and a nematic liq. crystal, E7, were studied over the course of polymn., i.e. as a function of the polymn. conversion. The effect of the mol. wt. of the epoxy oligomer on the initial temp.-concn. and the temp.-conversion phase diagrams was studied. An increase of the epoxy oligomer mol. wt. greatly reduces the initial liq. crystal soly. and brings the cloud point to earlier polymn. conversions, which were quantified. Thus the phase sepn. is markedly enhanced. The temp.-conversion phase diagrams were characterized at two isothermal polymn. temps. for one liq. crystal compn. (50 wt.). These diagrams (isotropic-nematic and nematic-isotropic transition temps.) obey ***master*** curves when the mol. wt. of the epoxy is varied. The size of the liq. crystal droplets decreases when the mol. wt. of the epoxy increases. This effect is mainly due to the viscosity increase resulting from the oligomer wt. increase. Viscosity measurements were made at intervals during polymn.
ST epoxy oligomer E7 liq crystal phase; phase sepn liq crystal epoxy
IT Cloud point
Phase diagram
Phase separation
Viscosity
(effect of mol. wt. of epoxy oligomer on phase sepn. of epoxy/E7 liq. crystal dispersion)
IT Epoxy resins, preparation
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
(effect of mol. wt. of epoxy oligomer on phase sepn. of epoxy/E7 liq. crystal dispersion)
IT Liquid crystals
(nematic; effect of mol. wt. of epoxy oligomer on phase sepn. of epoxy/E7 liq. crystal dispersion)
IT Liquid crystals
(transitions, nematic-isotropic transition; effect of mol. wt. of epoxy oligomer on phase sepn. of epoxy/E7 liq. crystal dispersion)
IT 63748-28-7, E7
RL: PRP (Properties)
(effect of mol. wt. of epoxy oligomer on phase sepn. of epoxy/E7 liq. crystal dispersion)
IT 110302-44-8P, DGEBA-Jeffamine D400 copolymer
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
(effect of mol. wt. of epoxy oligomer on phase sepn. of epoxy/E7 liq. crystal dispersion)
RE.CNT 17 THERE ARE 17 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE
(1) Aklonis, J; Introduction to polymer viscoelasticity 1982
(2) Borrajo, J; Polymer 1998, V39, P845 CAPLUS
(3) Dusek, K; J Polym Sci, Polym Symp 1975, V53, P29 CAPLUS
(4) Eloundou, J; Macromolecules 1996, V29, P6907 CAPLUS
(5) Eloundou, J; Macromolecules 1996, V29, P6917 CAPLUS
(6) Fox, T; Bull Am Chem Soc 1956, V2, P123
(7) Hirai, Y; SPIE 1990, V1257, P2 CAPLUS
(8) Kim, B; J Polym Sci, Part B: Polym Phys 1995, V33, P707 CAPLUS

(9) Kyu, T; Mol Cryst Liq Cryst 1996, V287, P27 CAPLUS
(10) Macosko, C; Macromolecules 1976, V9, P199 CAPLUS
(11) Masood, H; Polymer 1996, V37, P4795
(12) Montarnal, S; Ph D Thesis, INSA de Lyon 1987, P190
(13) Ono, H; Polym Bull 1995, V35, P364
(14) Siddiqi, H; Mol Cryst Liq Cryst, in the press 1998
(15) Utracki, L; Polymer Alloys and Blends 1990
(16) West, J; Mol Cryst Liq Cryst 1988, V157, P427 CAPLUS
(17) Williams, R; Adv Polym Sci 1997, V128, P95 CAPLUS

L3 ANSWER 3 OF 5 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1997:655031 CAPLUS
DN 127:353053
ED Entered STN: 15 Oct 1997
TI Liquid crystal display
IN Ikeda, Mitsushi; Fukunaga, Yoko
PA Toshiba Corp., Japan
SO Jpn. Kokai Tokkyo Koho, 16 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G02F001-136
ICS G02F001-1333; G02F001-1343
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 09258260	A2	19971003	JP 1996-66634	19960322
PRAI JP 1996-66634		19960322		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 09258260	ICM	G02F001-136
	ICS	G02F001-1333; G02F001-1343

AB The title display has contact holes for connecting TFTs and pixel electrodes, and an insulation film covered on the exposure regions of the pixel electrodes and common electrodes. The liq. crystal display may have multiple dye-contg. ***liq*** . ***crystal*** / ***polymer*** ***dispersion*** layers. The invention can assure good connection and offer a simple way for manuf. of the high quality liq. crystal display.
ST liq crystal display contact hole; insulation film liq crystal display
IT Acrylic polymers, uses
RL: DEV (Device component use); TEM (Technical or engineered material use); USES (Uses)
(forming insulation film in ***contact*** holes for covering ***exposure*** region of pixel and common electrode for liq. crystal display)
IT Liquid crystal displays
(having contact hole for connecting TFTs and pixel electrodes)
IT 1518-16-7, Tetra cyano quinodimethane 7440-02-0, Nickel, uses 25233-30-1, Polyaniline 30604-81-0, Polypyrrole
RL: DEV (Device component use); TEM (Technical or engineered material use); USES (Uses)
(coated on contact hole for connecting TFT and pixel electrode)

L3 ANSWER 4 OF 5 CAPLUS COPYRIGHT 2005 ACS on STN
AN 1994:521852 CAPLUS
DN 121:121852
ED Entered STN: 03 Sep 1994
TI Copier-platen liquid-crystal variable area-mask devices
IN Ueno, Osamu; Hiji, Naoki
PA Fuji Xerox Co Ltd, Japan
SO Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G02F001-1333
ICS G02F001-13; G02F001-1343; G03B027-62; G03G015-00; H04N001-04
ICA G03G015-04
CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 73

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 06051295	A2	19940225	JP 1993-135208	19930514
PRAI JP 1992-166703	A1	19920603		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 06051295	ICM	G02F001-1333
	ICS	G02F001-13; G02F001-1343; G03B027-62; G03G015-00; H04N001-04
	ICA	G03G015-04

AB The device comprises: a matrix array of electrooptical ***polymer*** - ***dispersed*** ***liq*** .- ***crystal*** microcells; and means for driving the individual microcells for forming various transparent patterns. The device is suited for use as a variable mask on the platen of a ***copying*** machine.

ST liq crystal microcell array platen mask

IT Optical imaging devices
(electrooptical ***liq*** .- ***crystal*** , ***polymer*** - ***dispersed*** microcell array, in variable-area platen masks, for copiers)

IT 25038-59-9, Polyethylene terephthalate, uses
RL: USES (Uses)
(***liq*** .- ***crystal*** ***polymer*** - ***dispersed*** microcell arrays, as substrate)

L3 ANSWER 5 OF 5 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1992:613850 CAPLUS

DN 117:213850

ED Entered STN: 28 Nov 1992

TI Composites of thermoplastic and liquid crystal polymers and their manufacture

IN Coffey, Gerald P.; Perec, Elena S.; Melamud, Lucy

PA BP America, Inc., USA

SO Eur. Pat. Appl., 24 pp.
CODEN: EPXXDW

DT Patent

LA English

IC ICM C08L101-00
ICS C08L067-03

CC 37-6 (Plastics Manufacture and Processing)
Section cross-reference(s): 75

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI EP 499387	A2	19920819	EP 1992-300827	19920131
EP 499387	A3	19921223		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, MC, NL, PT, SE				
CA 2060494	AA	19920814	CA 1992-2060494	19920131
CN 1067913	A	19930113	CN 1992-101629	19920212
JP 05214253	A2	19930824	JP 1992-26416	19920213
PRAI US 1991-654853	A	19910213		

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
EP 499387	ICM	C08L101-00
	ICS	C08L067-03

AB Chem resistant and mech. strong composites contg. .ltoreq.2% ***liq*** . ***crystal*** ***polymer*** (LCP) ***dispersed*** in a thermoplastic resin are manufd. by dispersing .gtoreq.2% solid LCP into molten thermoplastic and dilg. the ***masterbatch*** with addnl. thermoplastic polymer. Moldings, prepd. from 90/10 high-d. polyethylene (HDPE)-Vectra A950 (I, liq.-cryst. polyester) ***masterbatch*** with subsequent diln. by HDPE to I content 1%, had tensile strength 3518.9 psi, yield elongation 11.19%, break elongation .gtoreq.995% (for 3 of 6 samples), and good chem resistance.

ST polyethylene liq cryst polyester blend; chem resistance polyethylene polyester blend; dispersion liq cryst polyester polyethylene

IT Impact-resistant materials
(blends of liq.-cryst. polyesters and thermoplastic polymers as, with

good mech. strength and chem resistance)

IT Acrylic polymers, uses
Polyamides, uses
RL: USES (Uses)
(liq.-cryst. polyester blends with, with good mech. strength and chem resistance)

IT Plastics, molded
RL: USES (Uses)
(liq.-cryst. polyester blends, with good mech. strength and chem resistance)

IT Polyesters, miscellaneous
RL: MSC (Miscellaneous)
(liq.-cryst., blends with thermoplastic polymers, with good mech. strength and chem resistance)

IT Alkenes, polymers
RL: USES (Uses)
(polymers, liq.-cryst. polyester blends with, with good mech. strength and chem resistance)

IT Chemically resistant materials
(solvent-resistant, blends of liq.-cryst. polyesters and thermoplastic polymers as, with good mech. strength)

IT Liquid crystals, polymeric
(thermotropic, polyester, blends with thermoplastic polymers, with good mech. strength and chem resistance)

IT 25822-54-2, Rodrun 31072-56-7, Xydar 81843-52-9, Vectra A 950
RL: USES (Uses)
(blends with thermoplastic polymers, with good mech. strength and chem resistance)

IT 9003-07-0, Polypropylene
RL: USES (Uses)
(liq.-cryst. polyester blends with 5C08, with good mech. strength and chem resistance)

IT 9002-88-4, Polyethylene 9003-53-6 9010-79-1, Ethylene-propylene copolymer 25068-26-2, Poly(4-methyl-1-pentene) 26221-73-8, Dowlex 2045 108771-80-8, Barex 210
RL: USES (Uses)
(liq.-cryst. polyester blends with, with good mech. strength and chem resistance)

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(FILE 'HOME' ENTERED AT 15:39:55 ON 16 AUG 2005)

FILE 'CAPLUS' ENTERED AT 15:40:03 ON 16 AUG 2005
L1 2603 S (PDLC OR ((POLYMER(4A)DISPERS?)(5A)(LC OR LCD OR (LIQUID(4A)C
L2 5 S (COPY? OR COPIED OR MASTER? OR (CONTACT(5A)EXPOS?)) AND L1
L3 5 S (COPY? OR COPIED OR MASTER? OR DUPLICAT? OR (CONTACT(5A)EXPOS

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COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	51.12	51.33

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE ENTRY	TOTAL SESSION
CA SUBSCRIBER PRICE	-3.65	-3.65

STN INTERNATIONAL LOGOFF AT 15:43:06 ON 16 AUG 2005